

| Author  | Review article  | Citations | Journal                 | Year published | DOI or weblink  |
|---|---|-----------|-------------------------|----------------|---|
| Mackus, A. J. M.; Bol, A. A.; Kessels, W. M. M.   | The use of atomic layer deposition in advanced nanopatterning   | 221       | Nanoscale               | 2014           | <a href="https://doi.org/10.1039/c4nr01954g">https://doi.org/10.1039/c4nr01954g</a>                       |
| Cao, Kun; Cai, Jiaming; Liu, Xiao; Chen, Rong   | Review Article: Catalysts design and synthesis via selective atomic layer deposition  | 55        | J. Vac. Sci. Technol. A | 2018           | <a href="https://doi.org/10.1116/1.5000587">https://doi.org/10.1116/1.5000587</a>                         |
| Mackus, Adriaan J. M.; Merkx, Marc J. M.; Kessels, Wilhelmus M. M.  | From the Bottom-Up: Toward Atomic Area-Selective Atomic Layer Deposition with High Selectivity                              | 125       | Chem. Mater.            | 2019           | <a href="https://doi.org/10.1021/acs.chemmater.8b03454">https://doi.org/10.1021/acs.chemmater.8b03454</a> |
| Cao, Kun; Cai, Jiaming; Chen, Rong  | Inherently Selective Atomic Layer Deposition and Applications   | 31        | Chem. Mater.            | 2020           | <a href="http://doi/10.1021/acs.chemmater.9b04647">http://doi/10.1021/acs.chemmater.9b04647</a>           |
| Parsons, Gregory N.; Clark, Robert D.   | Area-Selective Deposition: Fundamentals, Applications, and Future Outlook   | 67        | Chem. Mater.            | 2020           | <a href="https://doi.org/10.1021/acs.chemmater.0c00722">https://doi.org/10.1021/acs.chemmater.0c00722</a> |
| Yarbrough, Josiah; Shearer, Alex B.; Bent, Stacey F.  | Next generation nanopatterning using small molecule inhibitors for area-selective atomic layer deposition                   | 5         | J. Vac. Sci. Technol. A | 2021           | <a href="https://doi.org/10.1116/6.0000840">https://doi.org/10.1116/6.0000840</a>                         |
| Bonvalot, Marceline; Vallee, Christophe; Mannequin, Cedric; Jaffal, Moustapha; Gassilloud, Remy; Posseme, Nicolas; Chevallieau, Thierry | Atomic and Molecular Layer Deposition Area Selective Deposition using alternate deposition and etch super-cycle strategies. | 0         | Dalton Trans.           | 2022           | <a href="https://doi.org/10.1039/d1dt03456a">https://doi.org/10.1039/d1dt03456a</a>                       |